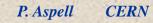
The Saltro chip design for TPC pad readout

Talk outline

The historical perspective.

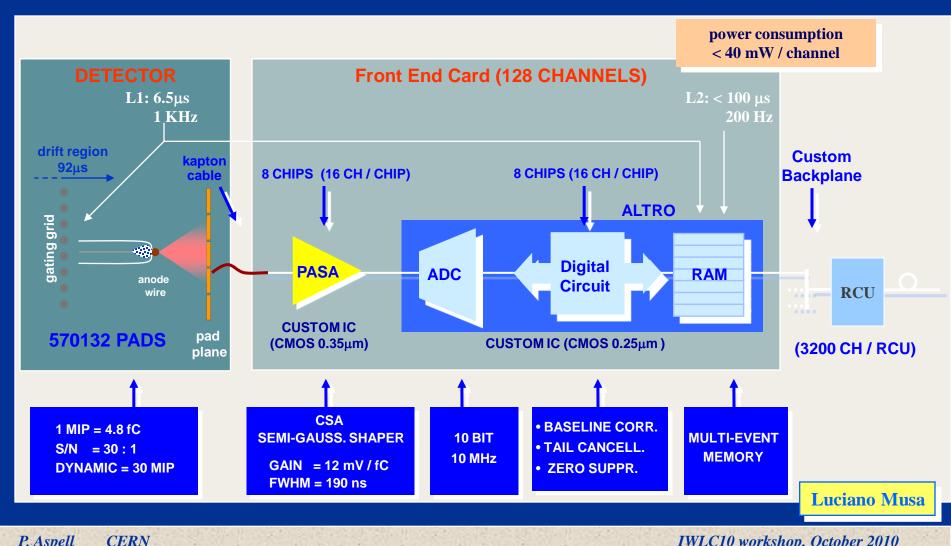
The SAltro demonstrator.

Projections and ideas for the future.



S-Altro architecture

Based on the existing PASA + Altro electronics designed for the Alice TPC



P. Aspell

SAltro Demonstrator

Goal:

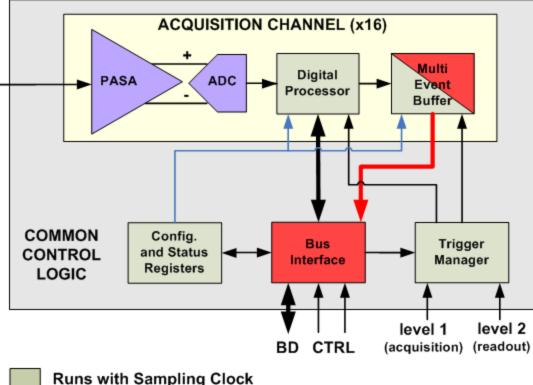
To demonstrate integration per channel of an analog frontend, an ADC and digital signal processing in a single chip.

Data processing of 100us of data sampled at 10MHz.

Prepare ideas for TPC readout in the ILC & CLIC

Luciano MusaS-Altro Specifications and ArchitecturePaul AspellCoordinator of demonstrator ASIC design.Massimiliano De GaspariFront-end + ADCHugo França-SantosADC coreEduardo GarciaData Processing & Control

SAltro Demonstrator Architecture



Runs with Readout Clock

Technology : IBM 130nm CMOS 8RFDM

- I6 Channels.
- Sampling rate 10, 20, 40MHz.
- ADC : 10 bits per sample.
- Level 1 commences sampling of a data-stream.
- 1008 (max) samples per data-stream.
- **DSP** for zero suppression.
- 40 bit word data packets containing timestamp and length.
- Possibility to by-pass DSP to have raw data.
- MEB (1024*40 RAM).
- Max. storage of 4 non-zero suppressed data-streams.

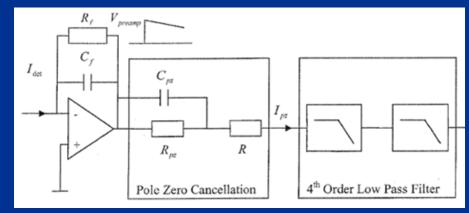
or

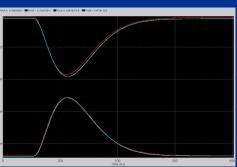
 Max. storage of 8 zero suppressed data-streams and/or with reduced datastream length.

- Level 2 must arrive before next Level
 1 in order to keep the data.
- <80 MHz readout on 40 bit CMOS</p>
- bus.

Saltro demonstrator Preamplifier/Shaper

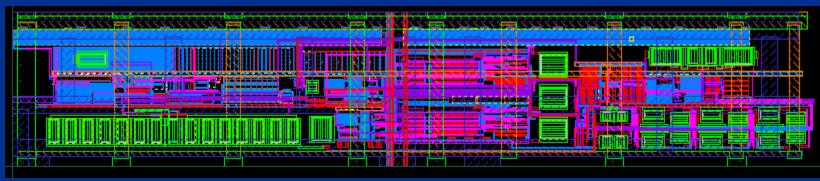
- Single-ended input, differential output
 - Dual polarity
 - 4 Gain options : 12, 15, 19 & 27mV/fC
 - 4 Shaping times : 30, 60, 90 & 120ns.
 - Linearity <1% to 150 fC
 - Shutdown mode (for power pulsing via a duty cycle clock)
 - Preamplifier enable (bypass shaper)





Size: 1100um X 210um P

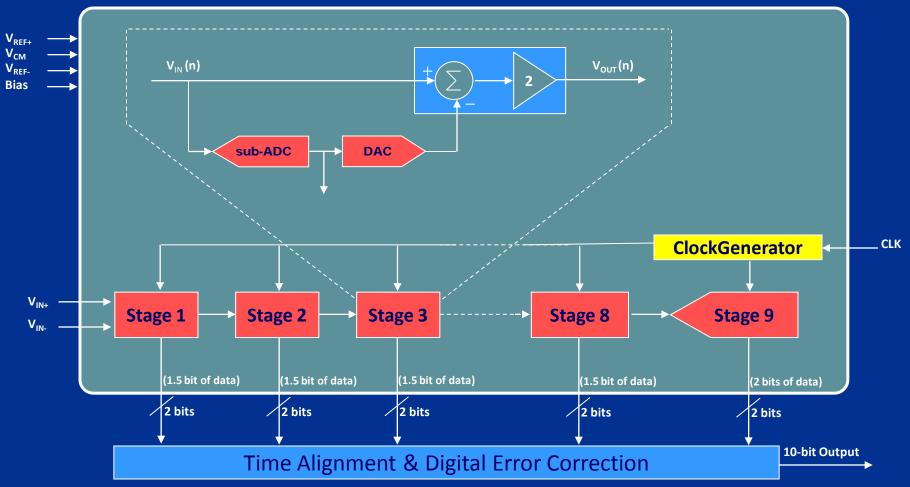
Power: 8.4mW/channel Supply: 1.5V



Massimiliano De Gaspari

IWLC10 workshop, October 2010

Pipeline ADC

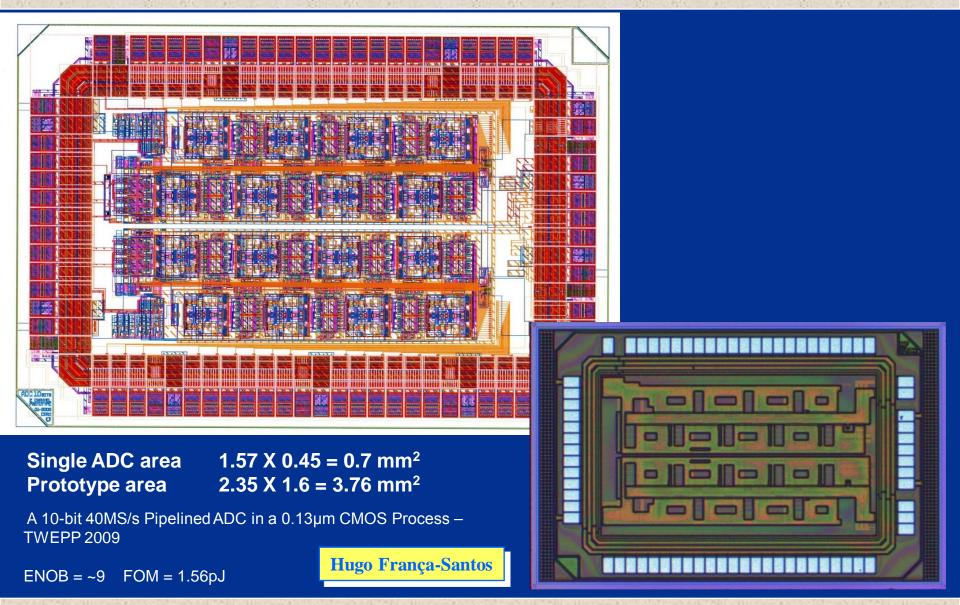


Hugo Franca-Santos, Massimiliano De Gaspari

10bit, 40MHz, 1.5V supply, 34mW power, 0.7mm² area

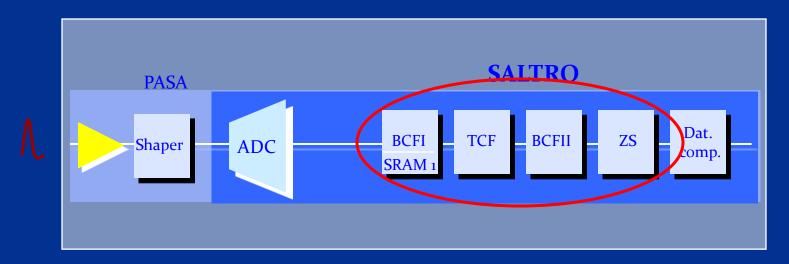
Power pulsing possible through bias pin.

Pipelined ADC: 2-Channel Prototype Layout



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DP functions



Baseline correction 1	Removes systematic offsets that may have been introduced due to clock noise pickup etc. The SRAM is used for storage of baseline constants which can then be used a look-up table and subtracted from the signal.
Tail cancellation	Compensates the distortion of the signal shape due to very long ion tails.
Baseline correction 2	Reduces low frequency baseline movements based on a moving average filter.
Zero suppression	Removes samples that fall below a programmable threshold.

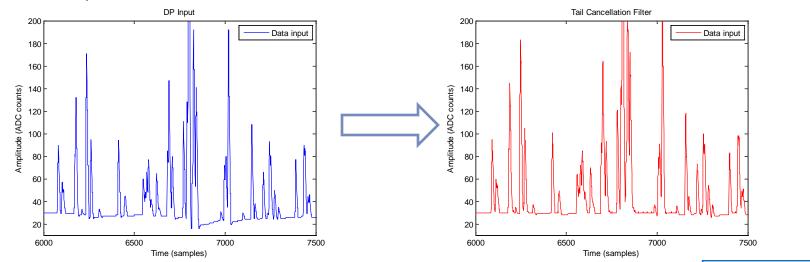
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Eduardo Garcia

DP simulation results

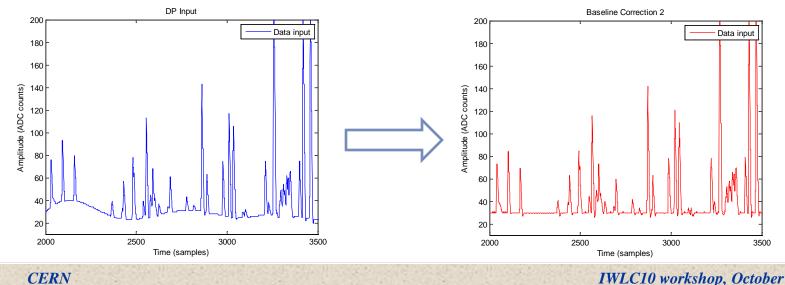
> TCF example test: rest of the filters are disabled.



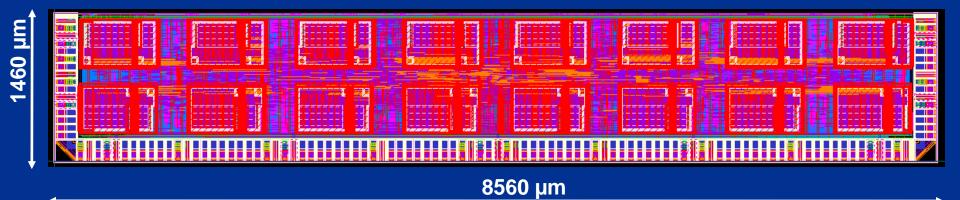
BC2 example test: rest of the filters are disabled.

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DSP, memories and data-formatter



Conditions:	
Static Analysis	Τος
VDD = 1.5V	Ter
Sclk = 50MHz	Vol
Rdoclk = 90Mhz	Sig

Toggle probability: 0.3 Temperature: 25 C Voltage variation: 10% Signoff verification

Encounter Statistical Power Analysis:

• Average power (considered in rail analysis): **118.62 mW**

S-ALTRO Demonstrator Floorplan

	N N N N N N N N N N N N N N N N N N N			Para Para Para Para Para Para Para Para			
Pad Pad Pad	PASA 200umX1100um		ADC 500umX1500um		Corr	Pad Pad Pad	
Pad Pad Pad Pad Pad	PASA 200umX1100um		ADC 500umX1500um		Corr	Pad Pad Pad Pad	
Pad Pad Pad Pad	PASA 200umX1100um		ADC 500umX1500um		Corr	Pad Pad Pad	
Pad Pad Pad	PASA 200umX1100um		ADC 500umX1500um		Corr	Pad Pad Pad	
Pad Pad Pad Pad Pad	PASA 200umX1100um		ADC 500umX1500um		Corr	Pad Pad Pad Pad	
Pad Pad Pad	PASA 200umX1100um		ADC 500umX1500um		Corr	Pad Pido Pad Fido Rad	
Pad	PASA 200umX1100um	E			_	Pad Pad Pad Pad Pad Pad	
Pad Pad Pad Pad	PASA 200umX1100um	Power Routing 8000um x 770um	ADC 500umX1500um		Corr	Pad Pad Pad	
Pad Pad Pad Pad Pad	PASA 200011X 1100011	1g 8000ur	ADC 500umX1500um		Clock Tree	Digital Signal Processing Pad 1670um x 8050um Pad	
Pad Pad	PASA 200umX1100um	ver Routir	ADC 500umX1500um		Corr	Pad Pad Pad Pad	
Pad Pad Pad	PASA 200umX1100um	Po	ADC 500umX1500um		Corr	Pod Pod Pod Pod Pod Pod	
Pad Pad Pad	PASA 200umX1100um		ADC 500umX1500um		Corr	Pad Pad Pad Pad Pad Pad	
Pad Pad Pad Pad	PASA 200umX1100um		ADC 500umX1500um		Corr	Pad Pad Pad Pad Pad	
Pad Pad Pad Pad	PASA 200umX1100um		ADC 500umX1500um		Corr	Pad Pad Pad	
Pad Pad Pad	PASA 200umX1100um		ADC 500umX1500um		Corr	Pad Pad	
Pad Pad Pad	PASA 200umX1100um		ADC 500umX1500um		Corr	Pad Pad Pad Pad	
Pad Pad Pad Pad	PASA 200umX1100um		ADC 500umX1500um		Corr	Pad Pad Pad	
Pad							

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16-channels:

PASA

ADC

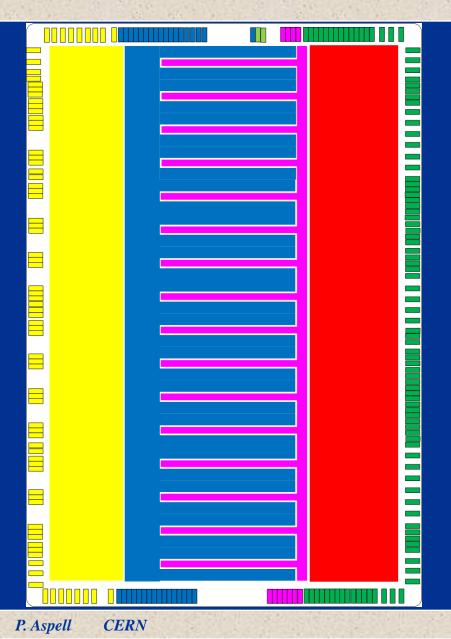
210um X 1100um 500um X 1500um

Digital Signal Processing 1670um X 8050um

The wide power routing ensures low IR power supply drop (10mV for the ADC)

> PASA ~8mW/ch, ADC 32mW/ch @40MHz Digital functions ~114mW Total power ~ 750mW

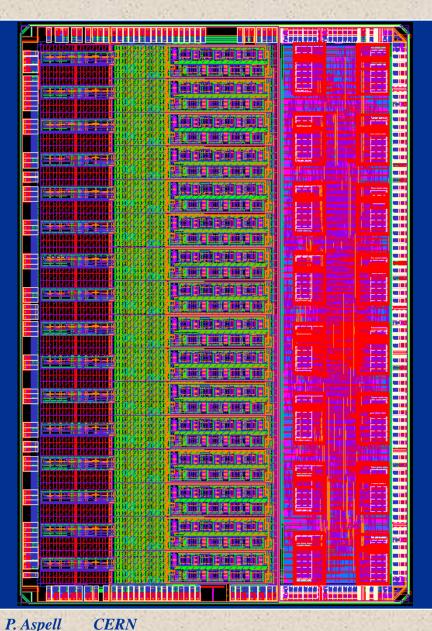
Power domains



Power domains: PASA analog ADC analog ADC digital Digital core Digital Pads

Power supply decoupling capacitors: 600pF /channel PASA 600pF /channel ADC analog 40pF /channel ADC reference voltages 80pF/channel ADC digital

Layout



Size: 5750um x 8560um (49.22mm²) MPW organised by CERN. Chip submitted in August 2010

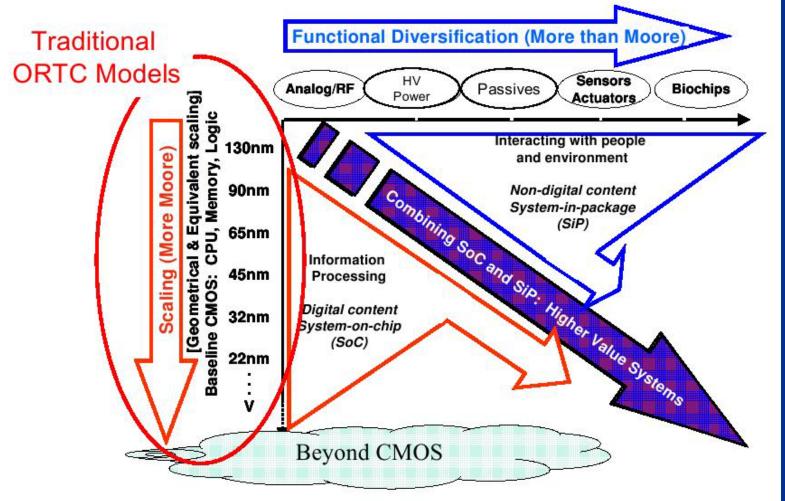
Expected back at the end of 2010.

The pad placement has been optimised for packaging within a TQFP 176 pin package.



The Future & Technology Trends

Moore's Law & More

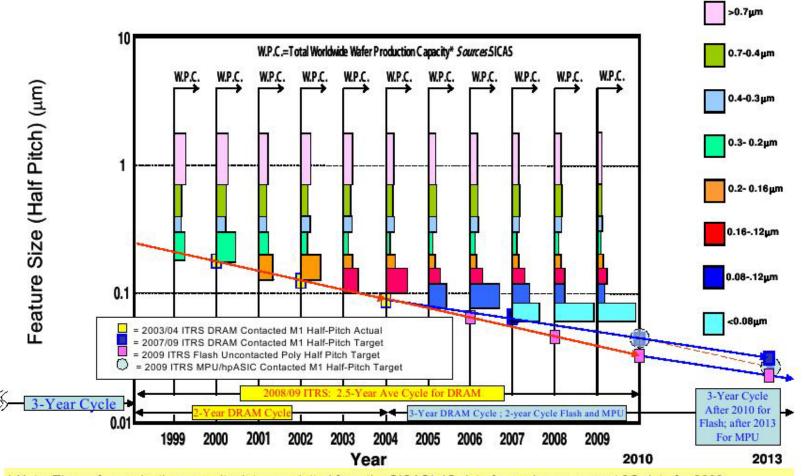


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Source : ITRS roadmap 2009

Technology Trends



* Note: The wafer production capacity data are plotted from the SICAS* 4Q data for each year, except 2Q data for 2009. The width of each of the production capacity bars corresponds to the MOS IC production start silicon area for that range of the feature size (y-axis). Data are based upon capacity if fully utilized.

Source : ITRS roadmap 2009

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Technology : CERN microelectronics group

- In addition to our current use of 0.25µm, 0.13µm and 90nm CMOS technologies CERN are now investigating 65nm CMOS technology.
- 12" wafers
- <10 Metal layers
- Vdd = 0.9V to 1.2V
- 840k gates/mm²
- Regular MPWs.
- LP process uses thicker gate oxide to GP to reduce leakage.

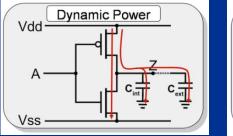
Standard Offering		65GP	65LP	65LPG		
			65LP	G	LP	
	Low	٢	٢		0	
	Medium Low		<u> </u>			
Vt	Standard	٢	٢	٢	٢	
	High	٢	0	<u> </u>	0	
	1.8V					
	1.8V (2.5V Under-drive)	0	٢	٢		
ю	2.5V	0	0	•		
	3.3V (2.5V Over-drive)	٢	٢	(>	
	3.3V	0	0			
	Ultra High Density (0.499)	0				
	High Density (0.525)	0	٢		0	
SRAM	High Current (0.62)	٢	<u> </u>	٢	0	
	Dual Port (0.97)	٢		0	0	
	Dual Port (1.158)	0			٩	

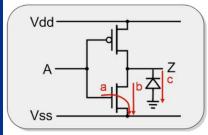
- CERN are now evaluating several 65nm design kits.
- Test structure submission planned for early 2011. To be followed by radiation studies.
- Standard cell libraries are available. They will probably need modification to be compatible with our needs.

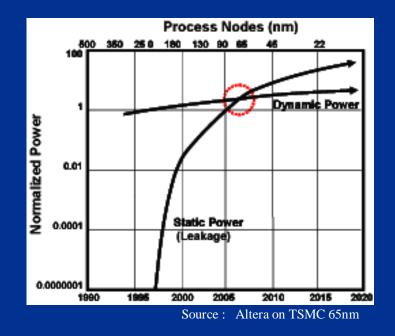
Digital

Scaling reduces source/drain capacitances and reduces power supply levels.

- Dynamic power goes down.
- $P_{dyn} = (C.Vdd^2 + Q_{short_circuit} Vdd) f$. activity
- However static power increases even in CMOS:
- Leakage currents increase including gate leakage current.
- Multiple power domains possible (vdd= 0.9V to 1.2V) depending on operating frequency required.
 - » Very high speed : Lowest Vt and max Vdd
 - » Moderate and Low Speed : higher Vt and reduced Vdd.
- The digital power consumption will take a larger % of total chip power in future designs compared to previous chips.



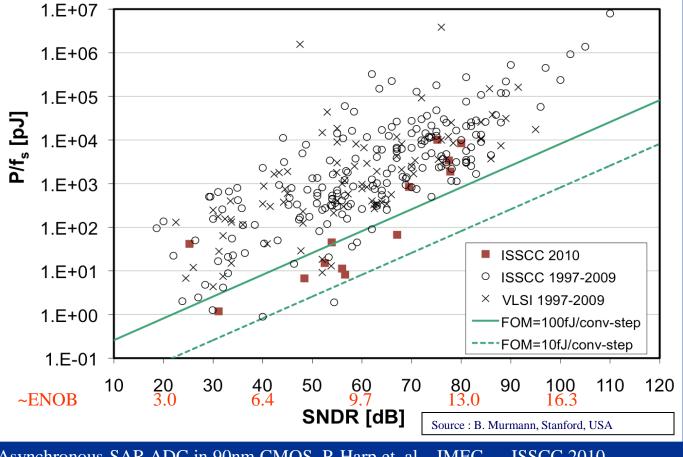




IWLC10 workshop, October 2010

ADC Trends

- FOM ~ P / $(2^{\text{ENOB}}, 2\text{BW})$
- 1pJ is high
- (~40mW @ ENOB 9, 40MS/s)
- 100fJ is good
- (~4mW @ ENOB 9, 40MS/s)
- 50fJ excellent
- (~2mW @ ENOB 9, 40MS/s)



State of the art :

A 30fJ/conversion 8b 0 to 10MS/s Asynchronous SAR ADC in 90nm CMOS. P. Harp et. al. IMEC ISSCC 2010 [They measured 69uW at 10MS/s,]

A 550uW 10b 40MS/s SAR ADC with Multistep Addition-only Digital Error Correction, Sang-Hyun Cho et al. CICC 2010 (FOM = 42 fJ/conversion) designed in 0.13um CMOS

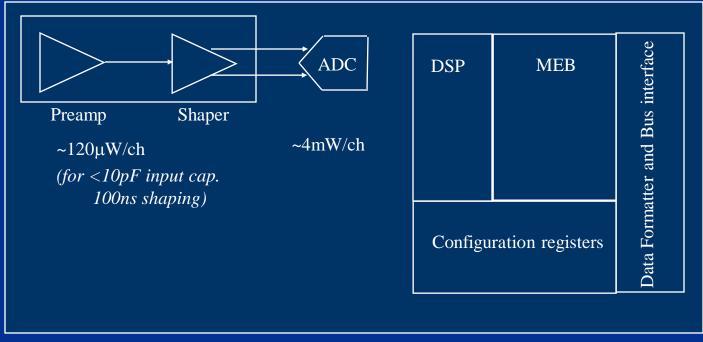
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Front-ends

- Front-end power can be very finely tuned but requires detailed knowledge of the sensor characteristics.
 - » Total input capacitance (sensor + coupling to neighbours + board) is required to optimise the input transistor current.
 - » Charge collection properties are required to make the correct choice of shaping time. If the shaping time is too small ballistic deficit will degrade S/N.
- Input transistor current scales with detector capacitance and charge collection time. Approx. $10\mu A/pF$ for 25ns shaping and ~ $2.5\mu A/pF$ for 100ns shaping.

Rough estimate of front-end power budgets				
Electrode capacitance	for 100ns shaping	for 25ns shaping		
1pF	12µW ??	48µW		
10pF	120µW	480µW		
20pF	240µW	1.6mW		
50pF	800µW	3.2mW		

Estimate for future power (static)



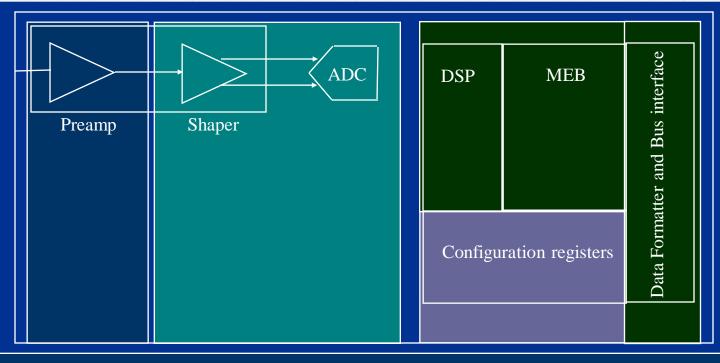
64 channels = Analog power ~ 263mW + Digital power ~ a few hundred mW. Approx. 400-500mW / chip.

128 channels = Analog power 526mW + Digital power ~ some hundreds mW. Approx. ~800-900mW / chip.

Should be possible to get < 7mW/ch for everything on a 128 ch chip.

Power management & pulsing may then be applied to reduce power further.

Power management : Power domains for reducing power further during "down" time (dynamic).



Preamp > Reduce current via bias control, important to maintain a low impedance on the electrode.

Shaper > Reduce current to approx. zero via bias control. Vdd could be maintained.

ADC > Stop clock and reduce current to approx. zero via bias control. Vdd could be maintained.

Configuration reg.s > Reduce Vdd to minimum voltage necessary to hold data. Current consumption limited to leakage currents.

Digital logic > Switched off by reducing Vdd to 0V.

Duty cycle of UP/DOWN time determined by a clock.

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- The SAltro architecture is derived from the Altro architecture currently used for TPC readout in ALICE.
- The SAltro demonstrator chip has been designed and submitted.
 - » Comprises 16 channels of Front-end + ADC + DSP on the same chip.
 - » Chip return back from foundry for beginning of 2011.
 - » Many things can be studied using the SAltro demonstrator :
 - GEM properties : capacitance, charge collection time, optimal shaping, channel to channel coupling etc.
 - Internal power pulsing on front-end and ADC via clock and bias control.
 - The power consumption of the present 16 channel chip is about the same absolute value as future chips with more channels. This makes the demonstrator useful for groups studying external power pulsing.
- The future looks favourably on the SAltro architecture.
 - » The industrial trend is with us continually looking for ways to reduce power.
 - » The ADC remains the critical element w.r.t. power, however state of the art ADCs are becoming more and more power efficient.
 - » Front-end power optimisation requires detailed knowledge of the sensor characteristics.
 - » Power management within a chip is now common place in modern industrial chips and could be a useful tool for power pulsing.